Serial No. 09/633,857
Art Unit: 1765

Applicant believes neither Nishizawa, Maley, Abelson nor Dubbelday, whether applied, either singly or in combination, teaches, discloses or suggests "controlling in real time " as set forth in amended claims 1, 11, let alone "substantially to the temperature profile and a gas flow profile" depicted in regions I, II, IV and VI of Figure 4.

Contrary to Applicant's invention, Abelson and Maley disclose monitoring, but not "controlling" as recited in instant claims 1, 11 (twice amended).

Thus, Applicant believes any rejection is overcome, without the introduction of new matter. See also, for example, page 12, lines 10-20, of the application as filed.

Accordingly, entry of this Amendment, reconsideration and allowance of claims 1, 3-11, 13-20 are solicited.

Attached hereto is a marked-up version of the changes made to the specification and claims by the current amendment. **This appendix is captioned "Version with Markings to Show Changes Made".**

Respectfully submitted,
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Attachment: Appendix - Version with Markings to Show Changes Made

11. (Twice Amended) Apparatus for depositing a film containing silicon on a crystalline silicon surface including

means for introducing a gas containing precursor material into a reaction vessel such that an activated species formed from said precursor material is adsorbed on said crystalline silicon surface, and

means for determining a partial pressure of hydrogen in residual gases as said activated species is deposited on said crystalline silicon surface,

[wherein said means for introducing includes means for introducing at least two gases according substantially to gas flow profiles depicted in regions I, II, V and VI of Figure 4]

means for controlling in real time at least one of temperature and mass flow of said precursor material in said reactor vessel in response to said partial pressure of hydrogen, wherein said means for controlling includes means for controlling in real time at least one of temperature and mass flow according to the temperature profile and a gas flow profile depicted in regions I, II, IV and VI of Figure 4.

US 096338570HP1

Creation date: 09-24-2003
Indexing Officer: KTRIEU - KIM TRIEU
Team: OIPEBackFileIndexing
Dossier: 09633857

Legal Date: 02-07-2003

No.	Doccode	Number of pages
1	CTNF	6

Total number of pages: 6

Remarks:

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